

Notice

Date: Monday, 14/11/2022

It is hereby informed to the students of M.Sc. – I and II, that First Term Internal Evaluation Examination is scheduled between 28th to 29th November 2022 in the Department of Physics.


Instructions:

- 1) Nature of question paper for M.Sc. – I: 05 MCQ's (05 Marks), 01 Short Answer Questions (05 Marks), 01 Long Answer Questions (10 Marks)
- 2) Nature of question paper for M.Sc. – II: 05 MCQ's (05 Marks), 01 Short Answer Questions (05 Marks), 01 Long Answer Questions (10 Marks)
- 3) Students should present before 15 minutes of the examination.
- 4) Answer sheets will be provided by the Department.
- 5) Strictly mention the Full Name and Roll number on Answer Sheet correctly.
- 6) All students should remain present for the Internal Examination as the examination will not be conducted afterwards in any case.

Sr. No.	Date	Class	Name of the Paper	Time
01	28/11/2022	M. Sc. – I	(01) Mathematical Physics	12 – 01 PM
			(02) Classical Mechanics	02 – 03 PM
02	28/11/2022	M. Sc. – II	(01) Nuclear and Particle Physics	12 – 01 PM
			(02) Thin Film Deposition and other Techniques	02 – 03 PM
03	29/11/2022	M. Sc. – I	(01) Quantum Mechanics I	12 – 01 PM
			(02) Condensed matter Physics	02 – 03 PM
04	29/11/2022	M. Sc. – II	(01) Solid State Physics – 01	12 – 01 PM
			(02) Solid State Physics – 02	02 – 03 PM


Coordinator




HOD, Physics
Head of the
Department of Physics
Vivekanand College, Kolhapur

Seat No.

Vivekanand College , Kolhapur (Autonomous).
M. Sc. Part-II (Semester- III) Internal Examination Oct/Nov.2022
Subject: Physics
Title: Nuclear and Particle Physics

Total Marks: 20

Time: 12.00 – 1.00 PM

Instructions: 1) All questions are compulsory.
2) Figures to the right indicate full marks.
3) Figures to the right indicate full marks.
4) Use of Scientific calculator or Log table is allowed.

Q. 1 Select most correct alternative

(05)

- i) Cosmic rays are produced in
- a) near moon b) near sun c) in volcanoes d) in outer space
- ii) Cyclotron is used to accelerates
- a) Protons b) electrons c) neutrons d) both (a) and (b)
- iii) G. M. counter is based on principle of
- a) transformer b) scintillation c) ionization d) gravitational
- iv) Wilson cloud chamber is generally useful for detecting
- a) cosmic rays b) X-rays c) cathode rays d) laser rays
- v) Protons and neutrons together called as
- a) Nucleons b) hyperons c) baryons d) epsilons

Q.2) Attempt any One

(10)

- i) Elucidate in brief "Cosmic Rays".
ii) What is matter & antimatter? Explain with special reference to positron and antiproton.

Q.3) Attempt any One

(5)

- i) Write a note on cosmic rays showers.
ii) Define
- i) Primary cosmic rays
 - ii) Secondary cosmic rays
 - iii) Soft component of cosmic rays
 - iv) Hard component of cosmic rays



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Shri Swami Vivekanand Shikshan Sanstha's
Vivekanand College (Autonomous) Kolhapur
Department of Physics M.Sc. II

2022-23

Attendance Sheet

Paper: Nuclear and particle physics

Date: 28/11/2022

Roll. No.	Name Of Candidate	Sign
1	Kshirsagar Vijaya Suresh	<i>[Signature]</i>
2	Kumbhar Pooja Prakash	<i>[Signature]</i>
3	Kurade Shubhangi Shivaji	<i>[Signature]</i>
4	Latthe Sammed Rajendra	<i>[Signature]</i>
5	Nikam Mrunali Tanaji	<i>[Signature]</i>
6	Patil Aakansha Bhimarao	<i>[Signature]</i>
7	Patil Anuja Dattajirao	<i>[Signature]</i>
8	Patil Rajat Jaywant	<i>[Signature]</i>
9	Patil Sanyogita Sanjay	<i>[Signature]</i>
10	Patil Shrutika Jaysing	<i>[Signature]</i>
11	Pirale Siddhant Deepak	<i>[Signature]</i>
12	Rajguru Supriya Dhanaji	<i>[Signature]</i>
13	Rajput Prerana Pundlik	<i>[Signature]</i>
14	Sakate Santosh Shripati	<i>[Signature]</i>
15	Sayyad Alsaba Javed	<i>[Signature]</i>
16	Shelar Avinash Sanjay	<i>[Signature]</i>
17	Sonkamble Rohan Raju	<i>[Signature]</i>
21	Sutar Pooja Vishwanath	<i>[Signature]</i>
22	Gaikwad Aishwarya Suryakant	<i>[Signature]</i>
23	Chougule Shraddha S.	<i>[Signature]</i>
24	Gaikwad Divya Ramesh	<i>[Signature]</i>
26	Gavade Sayali Shantaram	<i>[Signature]</i>
27	Gurav Rutuja Ravindra	<i>[Signature]</i>
28	Hirave Pravin Prakash	<i>[Signature]</i>
29	Jadhav Nikhil Sandeep	<i>[Signature]</i>
30	Jamadar Wahida Sardar	<i>[Signature]</i>
31	Kukade Seema Vishnu	<i>[Signature]</i>
32	Khandekar Pooja Sanjay	<i>[Signature]</i>
33	Khokar Raeez Rafiq	<i>[Signature]</i>
34	Khot Priyanka Balaso	<i>[Signature]</i>
35	Kondare Adinath Bhaskar	<i>[Signature]</i>
36	Kore Jyoti Vinayak	<i>[Signature]</i>

Name - Aishwarya Suryakant Gaikwad .

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-शिक्षणमहर्षी डॉ. बापूजी साळुंखे

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VIVEKANAND COLLEGE, KOLHAPUR (AUTONOMOUS)

SUPLIMENT

Suppliment No. :

Roll No. : 1334

Class : M.Sc II

11
20

Signature
of
Supervisor

Subject : Nuclear

Test / Tutorial No. : Internal No-1.

Div. : -

Que-1)

~~1) Soft~~

2) Maximum

3) Greater than

~~4) 1~~

~~5) Pions.~~

2



Que.3)

Cosmic Rays →

Cosmic Rays are rays encourage in earth's atmosphere from space. They do impact on earth's surface. There are two types of cosmic rays. they are.

- 1) Primary cosmic rays.
- 2) Secondary cosmic rays.

1) Primary cosmic rays →

The rays which enter earth's atmosphere direct from sun, thus called primary cosmic rays. they are produced due to continuous eruption on sun's surface. this eruption emits high amount of energy. that energy enters earth's atmosphere in form of rays. primary rays are uneven they are from energy.

2) Secondary cosmic rays →

Secondary cosmic rays are also enter in earth's atmosphere from space, but they are even and regular the eruption on sun's surface from rays but they are not regular or even so thus rays are not coming from sun.

In our milky way galaxy there are 10^{11} suns or stars are present. some are double stars as well as massive stars.

So recent assumption thus rays are come from inter interstellar space. cause emission of rays from stars of our galaxy is nearly similar to sun. Thus far away rays are also known as secondary cosmic rays. the intensity of secondary cosmic rays are less than intensity of primary cosmic rays.

3



Que. 2) Variation in intensity of cosmic rays.

Variation in intensity of cosmic rays is depends upon direction of rays. they are divided into three part according to direction as below-

- 1) Latitude - cosmic rays intensity
- 2) Altitude - cosmic rays intensity
- 3) East-west cosmic rays or azimuth effect

1) Latitude \rightarrow

- Latitude is rays which travel along direction of poles.

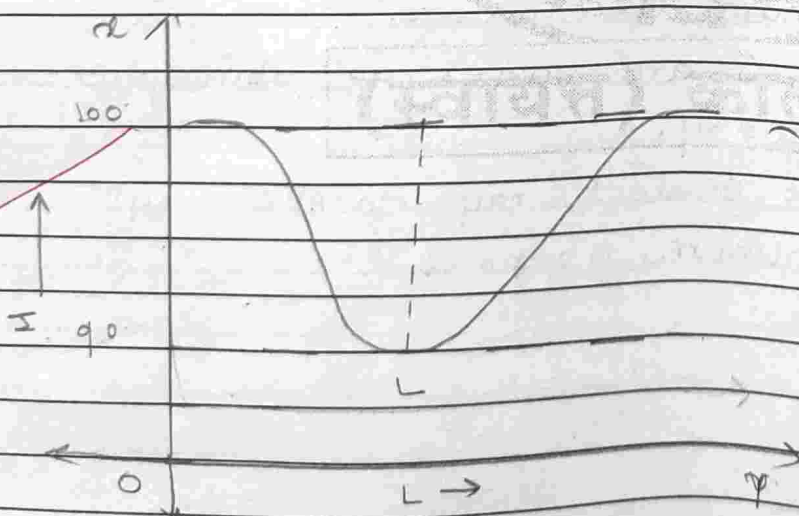
- Variation of intensity is in form of geomertic intensity.

- It is continuous in all region.

- Intensity is decrease as come from earth's equator.

- The cosmic ray intensity is minimum at 10° at intensity.

- Cosmic rays can intensity variation according to earth's magnetic intensity.

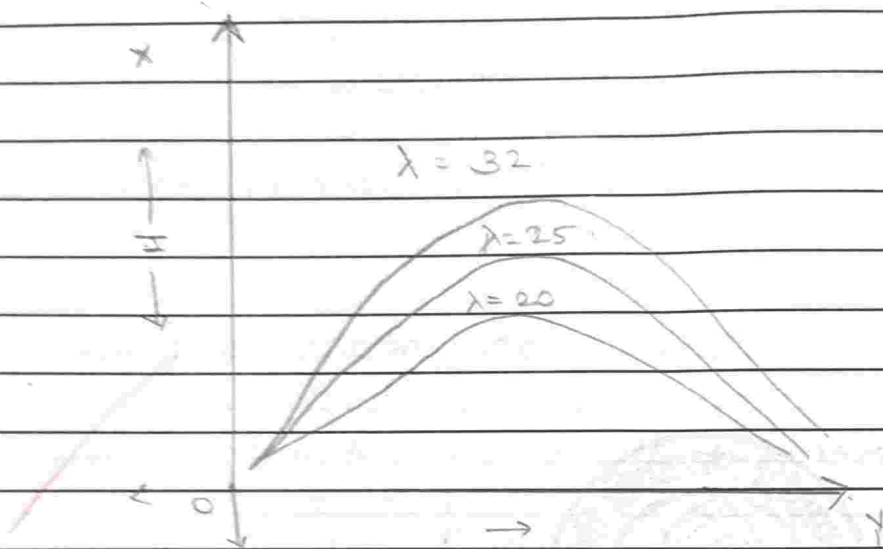


2) Altitude \rightarrow

- Intensity increases alternatively in atmosphere not maximum or minimum.



- Their intensity is maximum at poles.
- Intensity is increased by high altitude as 20k - 25k.
- ~~Intensity~~ The primary cosmic rays and secondary cosmic rays are present in altitude.



3) East-west intensity of cosmic rays [Azimuth Effect] →

- These are also present in earth's atmosphere. They show less intensity than other.
- These are less effective cosmic rays.
- These are maximum at equators.
- Their intensity varies as atmosphere is varies magnetic intensity.
- These are hard to detect rays cosmic rays.
- Intensity is minimum at poles.

6



Shraddha Sanjay Chaugule

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SUPPLIMENT

Signature
of
Supervisor

Suppliment No. :

$\frac{8}{20}$

Roll No. : 1332

Subject : Nuclear and Partical
Physics

Test / Tutorial No. :

Class : M.Sc - II (Physics)

Div. : -

Q1

~~①~~ soft

~~②~~ maximum

~~③~~ greater

~~④~~ 1

~~⑤~~ Pions

2

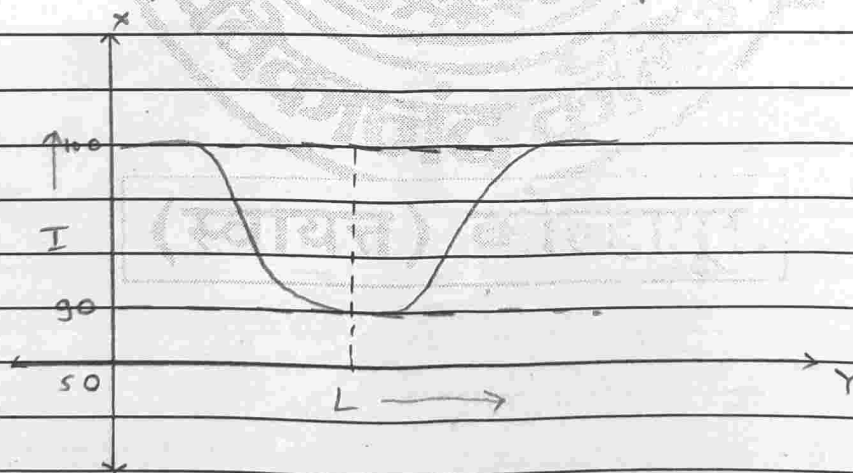
$\frac{8}{20}$



Q2. 2. The variation in intensity of cosmic ray

1] Latitude →

- ① It is a variation of cosmic ray intensity with geomagnetic intensity.
- ② The cosmic ray intensity is maximum at the uniform region.
- ③ it is decreases continuously more and more up to the equator.
- ④ The cosmic ray intensity is minimum at 10% less than intensity.
- ⑤ The cosmic ray can explain their variation of earth magnetic intensity.
- ⑥ The latitude is prove by the intensity of charged particles.
- ⑦ The ray goes deep at the atmosphere then intensity is fall and adsobtion is increases.



2] Altitude →

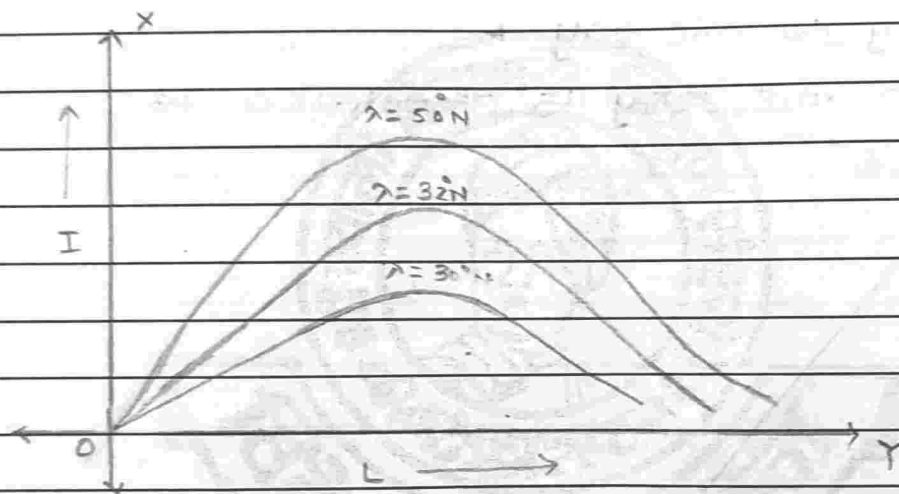
- ① The intensity increases alternately the altitude is also increase but the it not maximum at atmosphere.

② The intensity increase with increasing altitude at the height 20k to 25k.

③ The cosmic ray increase with intensity will increase and their geomagnetic latitude is increase.

④ The primary cosmic ray and secondary cosmic ray is present at this altitude.

⑤ The variation of intensity at atmosphere is earth magnetitude is parallel to the cosmic rays.



3] East - West intensity →

① The cosmic ray coming from west is greater than east this process is known as azimuthal effect.

② azimuthal effect is maximum at the equator.

③ In this effect cosmic rays coming from the west is 10% more than cosmic ray coming from the east.

④ The cosmic ray coming at earth's atmosphere is have various magnetic intensity.

this intensity is $\propto e^{\sigma}$ to the magnetic intensity.

⑤ I_w and I_E the intensity of west and east cosmic ray can be represented by the given eqⁿ.

$$\frac{I_w - I_E}{I_w + I_E}$$

Q3. 1.

Primary cosmic ray \rightarrow

cosmic ray is precipitated to

Vivekanand College, Kolhapur (Autonomous)

M.Sc. Part- II (Sem-III) Internal Examination (2022-2023)

Thin film deposition techniques &
Other Properties

Time - 11:00 am - 12:00 noon

Marks: 20

- Instructions:** 1) All the questions are compulsory.
2) Figures to the right indicate full marks.
3) Draw neat labeled diagrams wherever necessary.
4) Use of log table/calculator is allowed.

Q. 1) Select most correct alternative.

(5)

i) The ratio of the intensity of magnetization to the magnetizing field H is called as magnetic

.....

- A) permeability B) susceptibility C) induction D) moment

ii) The intensity of magnetization is given by

- A) M/A B) m/V C) m/A D) mA

iii) Hall voltage is directly proportional to.....

- A) current B) electric field C) magnetic flux D) temperature

iv) The high rate of deposition of thin film is possible with

- A) magnetic sputtering B) getter sputtering
C) triode sputtering D) diode sputtering

v) In laser photolytic photochemical deposition (LPD).... of sufficient energy are used to dissociate the molecules.

- A) photons B) neutrons C) hydrogen atoms D) electrons

Q.2 Attempt any One

(10)

i) What is meant by thin film? Give the different methods of thin film deposition by evaporation

ii) Derive an expression for diamagnetic susceptibility using quantum theory. Discuss the temperature dependence of susceptibility.

Q3. Attempt any One

(5)

i) Explain the effect of temperature on the conductivity of metals and semiconductors.

ii) Write note on Hall effect:



M.Sc. II

Internal Exam : Attendance sheet
Solid state physics - ~~II~~ I

Roll No.	Marks	Name	Sign
1331			
1332	16	shradha S. chougule	<u>Shradha</u>
1333			
1334	07	Aishwarya Suryakant Gaikwad	<u>Aishwarya</u>
1335	10	Divya Ramesh Gaikwad	<u>Divya</u>
1336	16	Gawade Sayali Shantaram	<u>Sayali</u>
1337	15	Gurav Rutuja Ravindra	<u>Gurav</u>
1338	09	Pravin Prakash Hirave	<u>Pravin</u>
1339	10	Nikhil Sandeep Jadhav	<u>Nikhil</u>
1340	10	Jamadar Wahida Saradar	<u>Wahida</u>
1341	16	Kakade Seema Vishnu	<u>Seema</u>
1342	13	Khandekar Pooja Sanjay	<u>Pooja</u>
1343	08	Khokhar Raveez Rafig	<u>Raveez</u>
1344	13	Khot Prayanka Balasa	<u>Prayanka</u>
1345			
1346	02	kondare Adinath Bhaskar	<u>Adinath</u>
1347	08	Kore Jyoti Vinayale	<u>Jyoti</u>
1348	11	Kshirsagar Vijaya Suresh	<u>Vijaya</u>
1349	15	Kumbhar Poala Prakash	<u>Poala</u>
1350	17	Kusade Shabhangi Shivaji	<u>Shabhangi</u>
1351			
1351	07	sammed Rajendra latthe	<u>Rajendra</u>
1352	07	Nikam Meenalini Tanaji	<u>Meenalini</u>
1353	10	Aakansha Bhimrao Patil	<u>Aakansha</u>
1354	17	Anuja Dattajirao Patil	<u>Anuja</u>
1355			
1356	11	patil sanyogita sanjay	<u>Sanyogita</u>
1357	15	Patil Shrutika Jayasingh	<u>Shrutika</u>
1358	15	Pirale Siddhant Deepak	<u>Siddhant</u>



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of
Supervisor

Subject :

Test / Tutorial No. :

Div. :

Suppliment No. :

Roll No. :

Class

1359 16 Rajguru Supriya Phandji

Rajguru

1360 16 Rajput Prerana pundlik

Rajput

1361

1362 07 Sayyad Alsaba Javed

Sayyad

1363 15 Avsharsh sanjay shelar

Avsharsh

1364

1365 10 Pooja vishwanath sutare

Pooja



Name - Anuja Dattajirao Patil

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of
Supervisor

Suppliment No. :

Roll No. : 1354

Class : MSc-II

Subject : SSP-I

Test / Tutorial No. :

Div. : $\frac{17}{20}$

Q1.

1. b) ~~Ga~~ (~~As~~)₃ + AsH₃

2. a) ~~partially~~ filled

3. b) ~~gains~~

4. b) ~~brumaethane~~ c) ~~zirconium~~

5. a) ~~chemical~~ reaction



Q.2.

1. Methods of film preparation.

The CVD technique has different deposition methods some are explained now:-

Nakamura reported the CVD technique to apply to form amorphous boron nitride film. The setup is consist of 2 adjustable leak walls.

The one end of wall is of ammonia NH_3 & the other is wall is of decaboran.

The deposition of film is on Ta or Si substrate.

The temperature of this technique is kept at 300°K to 1150°K .

The time took for this deposition was 30 min - 300 min.

The crystal structure of the film deposited was studied by x-ray diffraction.

A vertical cold wall low pressure CVD is used to prepare WSi_2 film.

Quartz bell jar of 24cm is used as working chamber to deposition.

graphite is coated with silica as a heat element.

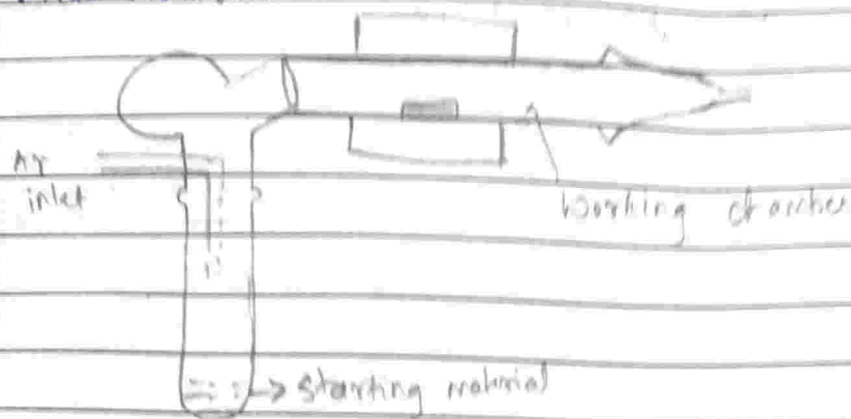
WF_6 & SiH_4 are used as reactant agents ^{gas} temperature of this is kept at 900°K .

And the chamber pressure is maintained at 10 Torr.

Heat flow is controlled by electric controll furnace.



Metal oxides film of like Al_2O_3 , CuO , Fe_2O_3 are deposited by decomposition on glass substrate.



Ar is passed through the inlet as shown in fig.

Ar flow rate is adjusted such that the fine Ar particles flow into the starting materials & then ~~such~~ so the starting elements should enter the working chamber.

The temperature is kept at $420^\circ K$. The thickness of the ~~su~~ film of on substrate is $10-20nm$.

low pressure CVD is used to prepare the Borophosphosilicate glass film.

Some source materials used for this are Tetraethyl orthosilicate, tetramethyl benzilene & tetramethyl propane.

The source materials are volumetrically measured & mixed together to form a ~~solut~~ mixture.

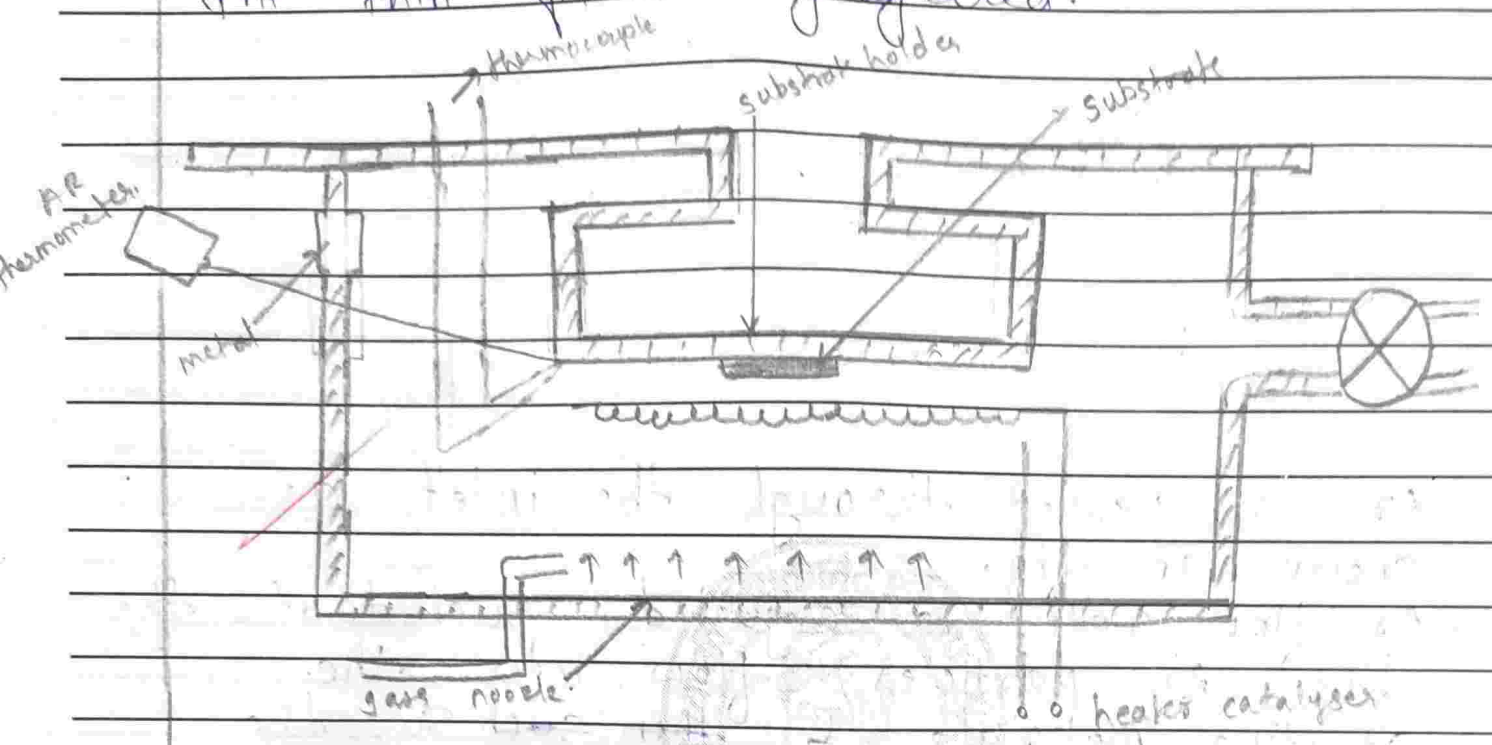
The mixture is delivered to the reactant by using syrin pump.

The exist side of the reactant is heated so that the liquid in it



vaporizes.

The vapours fill on the substrate & the thin film is prepared.



Other low temperature CVD method is catalyser experiment which is use to prepare amorphous semiconductor film.

The decompose chamber is made of steel & the film is kept substrate holder is kept such that heat & cool is done by air jet behind it.

The thermocouple is placed near the substrate also that the temperature of it is known.

The heat catalyses is placed parallel to the substrate holder.

The decomposition takes place & the substrate settle on the substrate or substrate holder kept at center of chamber.

This is used to prepare nitride films. temperature of 300K.



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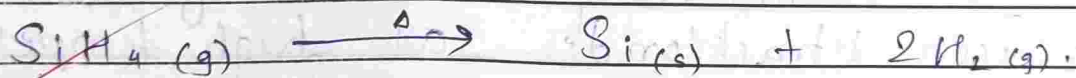
Div. :

Q.3.

1. Common CVD reactions:-

Thermal decomposition reaction.

Silane gas is heated to get silicon.
The decomposition of silane gas takes place as we used here silane gas.



Same is done to get titanium from TiI_2



Reduction reaction:

Reduction reaction is gain of electrons.
Chlorides are more commonly used halides because they are high volatile & easily purified by fractional distillation.
Hydrogen reduction is not applied to certain metals like Ti & Al. because

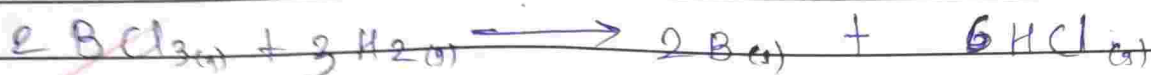


Their halides are very stable.



Silicon tetrachloride goes through reduction to form silicon.

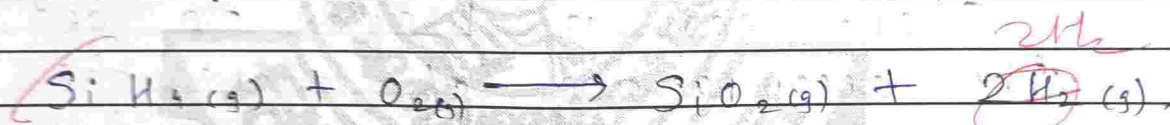
Similarly for Boron trichloride BCl_3 is as



Oxide formation:

In this formation oxide films are formed.

SiO_2 is prepared by oxidation of silane ~~gas~~ with oxygen in atmospheric pressure.



There is another way of oxidation of SiO_2 by silicon tetrachloride at high temperature.



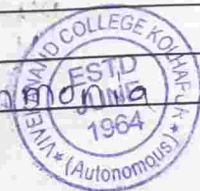
As we know oxidation is loss of electrons.

Nitride & Carbide formation:-

The formation of nitride & carbide depends on change in parameters like temperature & pressure.



Boron trichloride is reacted with ammonia

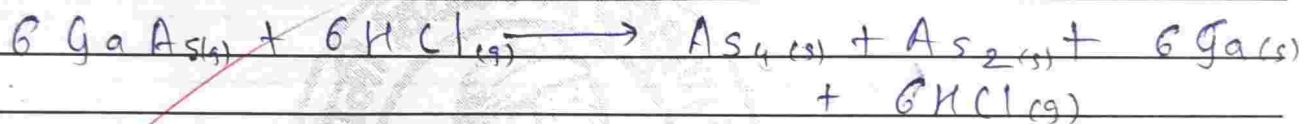
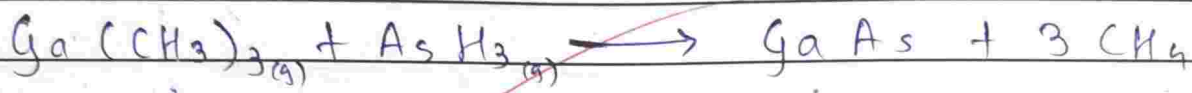


to get Boron nitride.

Similarly for carbide formation. for titanium tetrachloride.



Compound formation:-



decomposition of compound in 3 to 5 group. forms organometallic reactions.

स्वायत्त कॉलेज पर.



Name - Shubhangi Shiveji Kurade

D-16-11-22

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SUPPLIMENT

Signature
of
Supervisor

Suppliment No. : 1

Roll No. : 1350

Class : M.Sc II

Subject : Thin Solid films deposition & Properties.

Test / Tutorial No. : Internal exam.

Div. :

17
20

Q.1

1) → b) $Ga(CH_3)_3 + AsH_3$

2) valence shells of noble gas are completely filled

3) According to electronic concept reduction is defined as process in which an atoms / ions gains one or more electrons.

4) → Zirconium

5) CVD thin films are formed on a heated substrate via chemical reaction & physical reaction



2
1) The film preparation are different types:

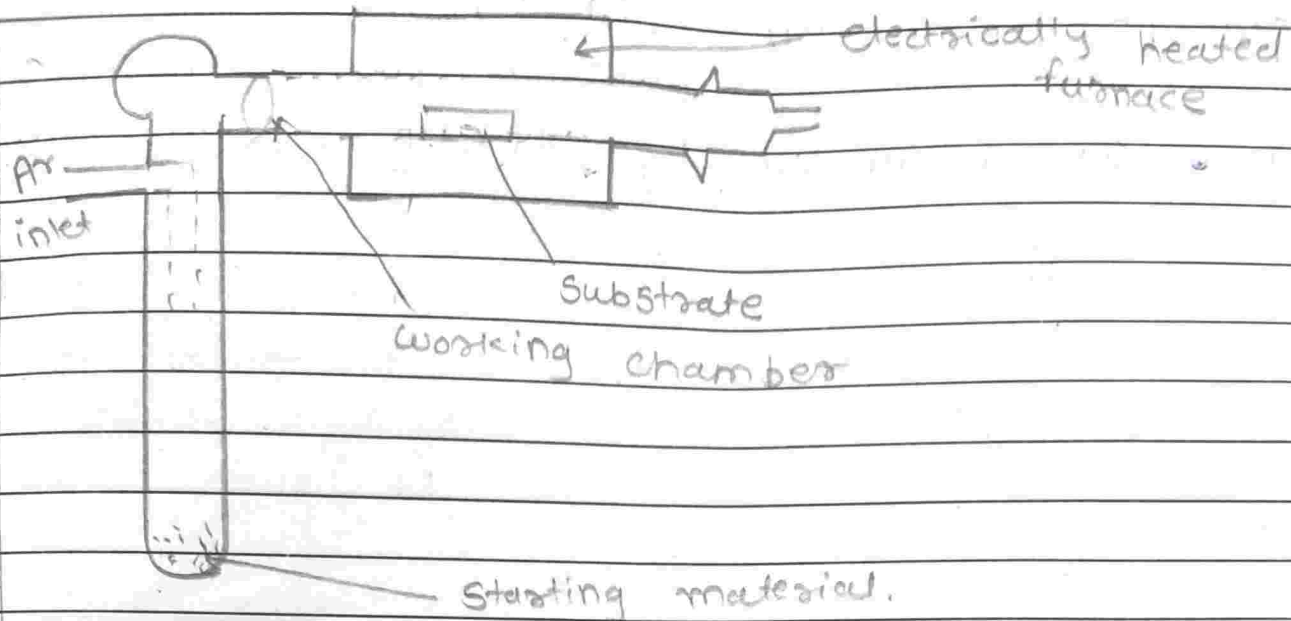
i) Nakamura reported has been apply to form amorphous boron nitride film. His set up is controlled by adjustable two leak valves. one is for NH_3 and other one for B_2H_6 . The film is deposited on Ta or Si substrate. The substrate is heated to the temperature at $300 - 1150^\circ\text{C}$. and deposition time of the film preparation is 30 - 300 minutes. The crystal structure on thin film substrate are studied by X-ray diffraction.

ii) A cold wall low pressure CVD. technique. WSi₂ it has a ~~vertical~~ vertical cold wall low WSi₂ pressure technique. A ~~vertical~~ vertical bell jar are 24 cm in diameter are used in a reaction as a reaction chamber.

- Graphite sheet coated with silica they act as a heater element.
- The WFC is diluted at silane gas (SiH_4) they act as a reactor gas. The substrate temperature is 400°C .

iii) Metal oxide film preparation like Al_2O_3 , In_2O_3 The metal oxide film preparation starting material are used they are in fine powder formation. Ar gas flow rate are used as shown in fig:





Ar gas is pass through the inlet. Ar particles are comes to the Starting material and starting get Comes in working chamber. The starting material particles are working chamber. Some particles are settle on substrate and other particles are hold at center of the working chamber. The substrate is in electrically heated furnace at 420°C . The thickness of the thin film is $10-20\text{ nm}$. The substrate is kept at 420°C for 2 Hours. After over a night thin films are annealate.

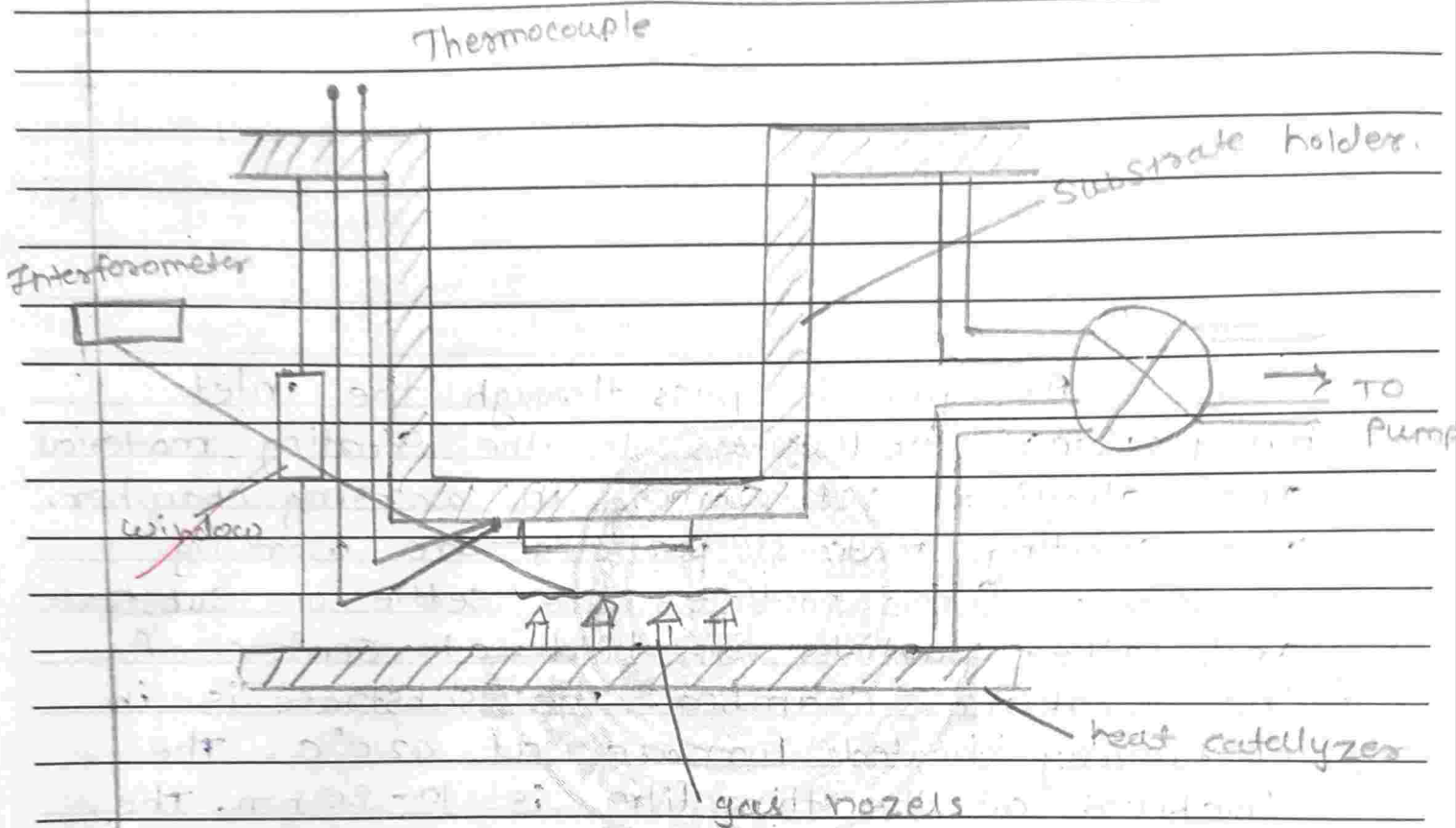
iv) Nitride films Low temperature CVD.

low temperature CVD it is the mixture of vapours. The vapor mixture of the ^{Trimethyl} nitrides are deliver at reactor gas by siringe pump. The ~~gl.~~ Glass substrate are used in low temp. CVD of film preparation. The vapors of the mixture are set on the substrate and. the thin film was deposited on glass substrate. It is used two leak valves, leak valves looses the exist the vapors and settle on substrate.



v) Low pressure CVD (LPCVD)

Low pressure CVD is also called Catalytic CVD. It is denoted by GATCVD or CLT CVD.



Reaction chamber is made up of steel. In this process, Thermocouple, Substrate holder, gas nozzles, heat catalyzer are involved.

The gas nozzles are heated to the substrate. substrate holder are kept to the substrate.

Heat catalyzer are parallel to the substrate. catalytic reaⁿ are involved in LPCVD.

Vivekanand College, Kolhapur (Autonomous)

M.Sc. Part- II (Sem-III) Internal Examination (2022-2023)

SOLID STATE PHYSICS- I

Thin film deposition techniques

Electric & Magnetic Properties

Time - 12:00 noon - 01:00 pm

Marks: 20

- Instructions:** 1) All the questions are compulsory.
2) Figures to the right indicate full marks.
3) Draw neat labeled diagrams wherever necessary.
4) Use of log table/calculator is allowed.

Q. 1) Select most correct alternative.

(5)

i) The intensity of magnetization is given by

- A) M/A 3) m/V C) m/A D) mA

ii) Hall voltage is directly proportional to.....

- A) current B) electric field C) magnetic flux D) temperature

iii) Hall effect can be used to determine.... of charge carrier

- A) polarity B) temperature C) viscosity D) strength

iv) The ratio of the intensity of magnetization to the magnetizing field H is called as magnetic

- A) permeability B) susceptibility C) induction D) moment

v) Paramagnetic Curie temperature in Kelvin for iron is equal to

- A) 2195 B) 495 C) 895 D) 1095

Q.2 Attempt any One

(10)

i) Explain the cathode sputtering. Discuss the factors affecting glow discharge.

ii) Explain process variables in CVD method. Explain preparation of a Si by photo-CVD method.

Q3. Attempt any One

(5)

i) What are the applications of plasma enhanced CVD

ii) Explain electron beam evaporation for obtaining high quality films.



Internal Exam. 2021-23 : Attendance sheet

Paper - TF Technology

Name	Name	Markes	Sign
Roll No.	Roll No.		
1331	Ab	Absent	
1332	shradha sanjay chougule	09	Chougule
1333	Ab	Absent	
1334	Aishwarya Suryakant Galkwad	10	Galkwad
1335	Divya Ramesh Galkwad	10	Galkwad
1336	Gawade Sayali Shantaram	17	Sayali
1337	Gurav Rutuja Ravindra	08	Gurav
1338	Hirave Pravin Prakash	15	Hirave
1339	Nikhil Sandeep Jadhav	08	Jadhav
1340	Jamaadar Wahida Saradar.	10	Saradar
1341	Kakade Seema Vishnu	12	Kakade
1342	Khandekar Pooja Sanjay	08	Pooja
1343	Khokhar Deepak Rafiq.	08	Khokhar
1344	Khot Poojanka Balaso	13	Khot
1345	Ab.	Absent	
1346	Kondare Adinath Bhaskar	14	Kondare
1347	Kore Jyoti Vinayak	08	Kore
1348	Kshirsagar Vijaya Suresh	05	Kshirsagar
1349	Kumbhar Pooja Prakash	11	Kumbhar
1350	Kusade Shubhangi Shivaji	16	Kusade
1351	Sammed Rajendra Lathe	12	Sammed
1352	Nikam Meenal Tanaji	08	Nikam
1353	Aakansha Bhimaro Patil	10	Aakansha
1354	Anuja Dattajirao Patil	10	Anuja
1355	Patil Rajat Jaywant	05	Patil
1356	Sunyogita Sanjay Patil	09	Sunyogita
1357	Shrutika Jaysing Patil	12	Shrutika
1358	Siddhant Deepak Pirale	16	Siddhant
1359	Supriya Dhanaji Rajguru	19	Supriya
1360	Prerana Pundlik Rajput	08	Prerana



Rolls number :

1361				
1362	Sayyad	Aiseba	Javed	08 Rayyad
1363	Avinash	Sanjay	Shelar	11 AVS
1364		Ab		Absent Absent
1365	Pooja	Vishwanath	sutar	09 Putas

~~Case~~
16.11.2022



15/11/2022

Rajguru Supriya Dhanaji

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-शिक्षणमहर्षी डॉ. बापूजी साळुंखे

19/20
one

Shri Swami Vivekanand Shikshan Sanstha Kolhapur's

VIVEKANAND COLLEGE, KOLHAPUR (AUTONOMOUS)

SUPPLIMENT

Signature of Supervisor	
Subject : Thin film Deposition technology	
Test / Tutorial No. :	
Div. :	

Suppliment No. : 01

Roll No. : 1359

Class : M.SC-II

Q.1)

1) ~~Anti-stokes~~

2) polarization

3) vibrational

4) magnetic field

5) $\Delta E = +g\mu_B B_z$

Q.2)

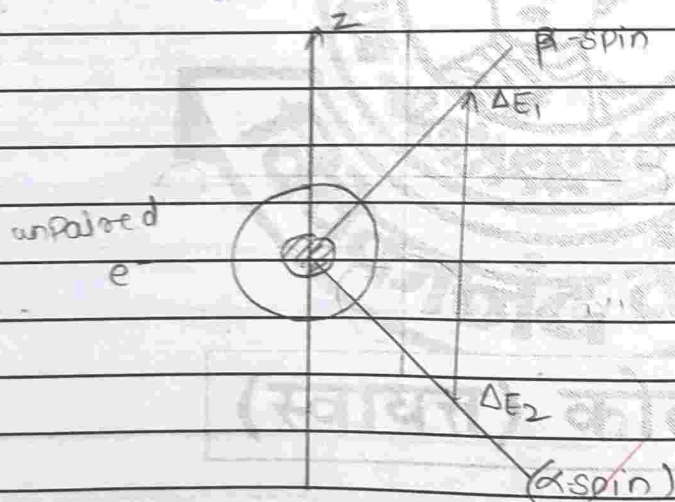
ii) Electron Spin Resonance Spectroscopy :

• The electron spin resonance in incident ray of photon we get back reflected and scattered.

• The properties of ESR is study we based on unpaired e^- with their technique case.



- ESR is absorption of an microwave radiation with unpaired electron with applied strong magnetic field.
- In ESR technique the splitting of magnetic energy level is done due to applied static magnetic field.
- ESR is based upon atomic number of odd number of electron.
e.g: NO, CO₂
- free radicals are unpaired electrons.
- In ESR technique we used paramagnetic materials.
- The splitting of the energy level is depends on the applied magnetic field.



- when the spin quantum number $S = \pm 1/2$ & spin magnetic spin quantum number $m_s = \pm 1/2$
- If we written as spin angular momentum \vec{S} .

$$\vec{S} = \sqrt{S(S+1)} \cdot \frac{h}{2\pi}$$

where, $S = \pm 1/2$

$$\vec{S} = \sqrt{1 \left(\frac{1}{2} + 1 \right)} \cdot \frac{h}{2\pi}$$



$$S = \frac{\sqrt{3}}{4} \cdot \frac{h}{2\pi}$$

- The magnetic spin angular momentum is given by $m_s \cdot \frac{h}{2\pi}$

Here, magnetic spin momentum, $m_s = \pm \frac{1}{2}$

- Therefore, the total spin angular momentum is

$$\frac{\sqrt{S(S+1)} \cdot h}{2\pi} = m_s \cdot \frac{h}{2\pi}$$

- The z-component is orientation angle θ ($\cos\theta$) with splitting of e^- unpaired e^-

$$\frac{\sqrt{S(S+1)} \cos\theta \cdot h}{2\pi} = m_s \cdot \frac{h}{2\pi}$$

$$\therefore m_s = \sqrt{S(S+1)} \cdot \cos\theta$$

- The magnetic moment due to unpaired e^- is

$$\mu = -g \left(\frac{e}{2m} \right) \sqrt{S(S+1)}$$

Here, g = lande g factor

e = charge of e^-

m = rest mass of e

$$\therefore \mu = -g \left(\frac{eh}{4\pi m} \right) \sqrt{S(S+1)}$$

$$\therefore \mu = -g \mu_B \cdot B_z$$

we get the energy difference,

$$\Delta E = -\mu \cdot B_z$$

$$= -g \left(\frac{eh}{4\pi m} \right) m_s \sqrt{S(S+1)} B_z$$

$$\Delta E = -g \mu_B B_z m_s B_z$$

$$\text{Here, } m_s = +\frac{1}{2} \text{ \& } m_s = -\frac{1}{2}$$



$$E_{+1/2} = + \frac{1}{2} g \mu_B \cdot B_z$$

$$E_{-1/2} = - \frac{1}{2} g \mu_B \cdot B_z$$

$$\therefore \Delta E = E_{+1/2} - E_{-1/2}$$

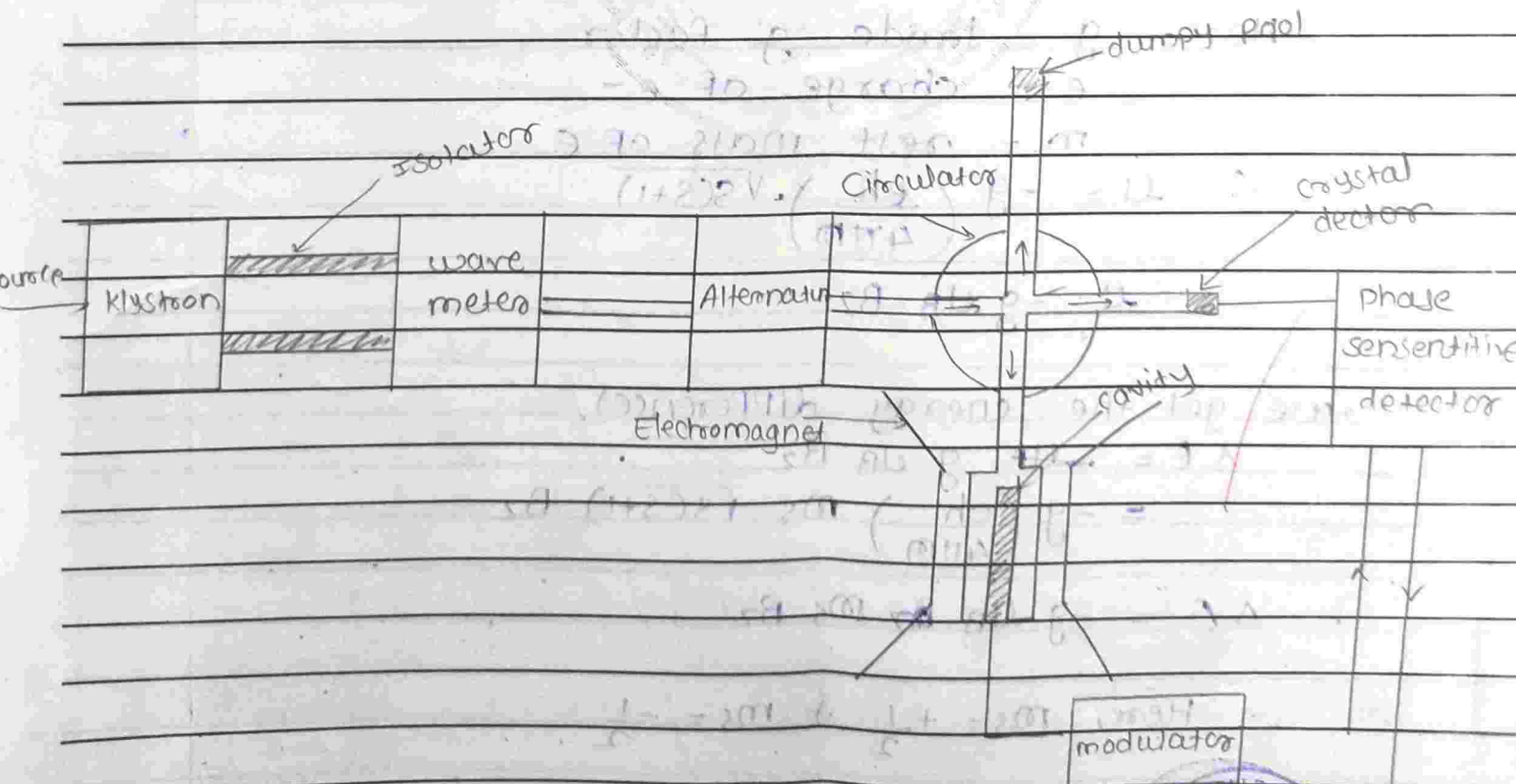
$$\Delta E = g \mu_B B_z$$

$$\text{But, } \Delta E = h\nu$$

$$h\nu = g \mu_B B_z$$

$$\nu = \frac{g \mu_B B_z}{h}$$

Construction of ESR Spectrometer:



15/11/2022

Rajguru Supriya Dhanaji

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Shri Swami Vivekanand Shikshan Sanstha Kolhapur's

VIVEKANAND COLLEGE, KOLHAPUR (AUTONOMOUS)

SUPPLIMENT

Signature
of
Supervisor

Subject : Thin Film Deposition
technology

Test / Tutorial No. :

Div. :

Suppliment No. : 02

Roll No. : 1359

Class : M.Sc-II

1) Source :

The input of single of Klystron. They are oscillate a small input. It is passing through a monochromatic light.

2) Isolator :

The frequency collected and converts
It is ferric material and dielectric filter.
Isolator we can generators the same oscillation between single.

3) wave meter :

The frequency single collected and converts the only one direction of single.

4) Attenuator :

The frequency single at provided the low power same supply. and single passed through the circulator.



5) Circulator:-

The single circulation the to circulated & through out the circulator detector, crystal detector.

6) Cavity:-

The electron spin resonance spectrometer the sample is located.

7) Crystal detector:-

Here a crystal detector we used as silicon material. they are incident on sample.

8) Electromagnet:-

Here we the homogenous magnetic field they are provides high power supply.

9) Phase sensitive detector:-

The phase sensitive detector is optical device they are measure of phase difference betⁿ the sample.

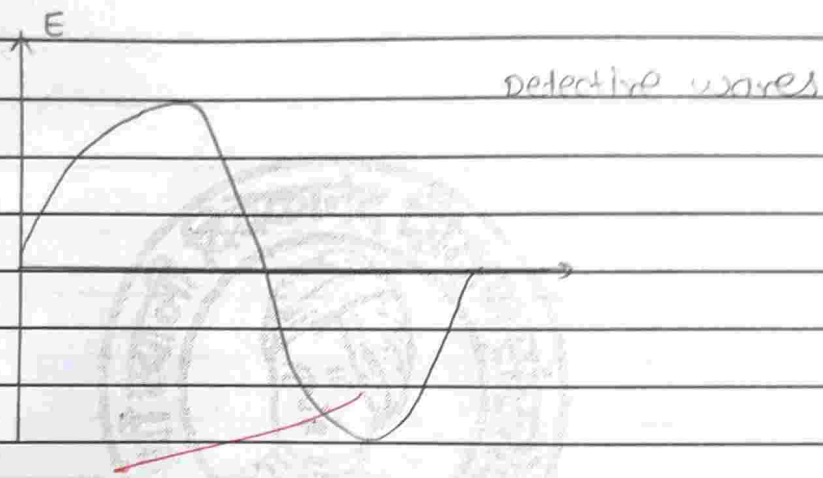
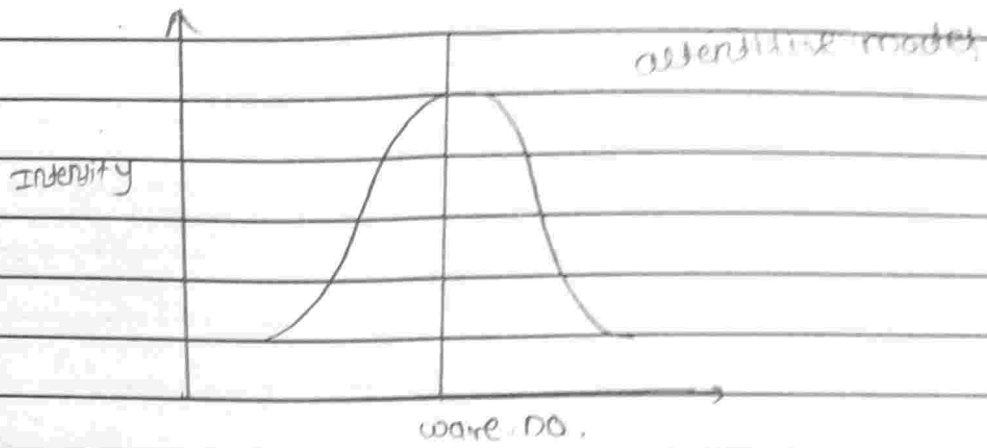
10) Modulator:-

modulator it is electric device. They are also used in a logic gate.

11) Collector:-

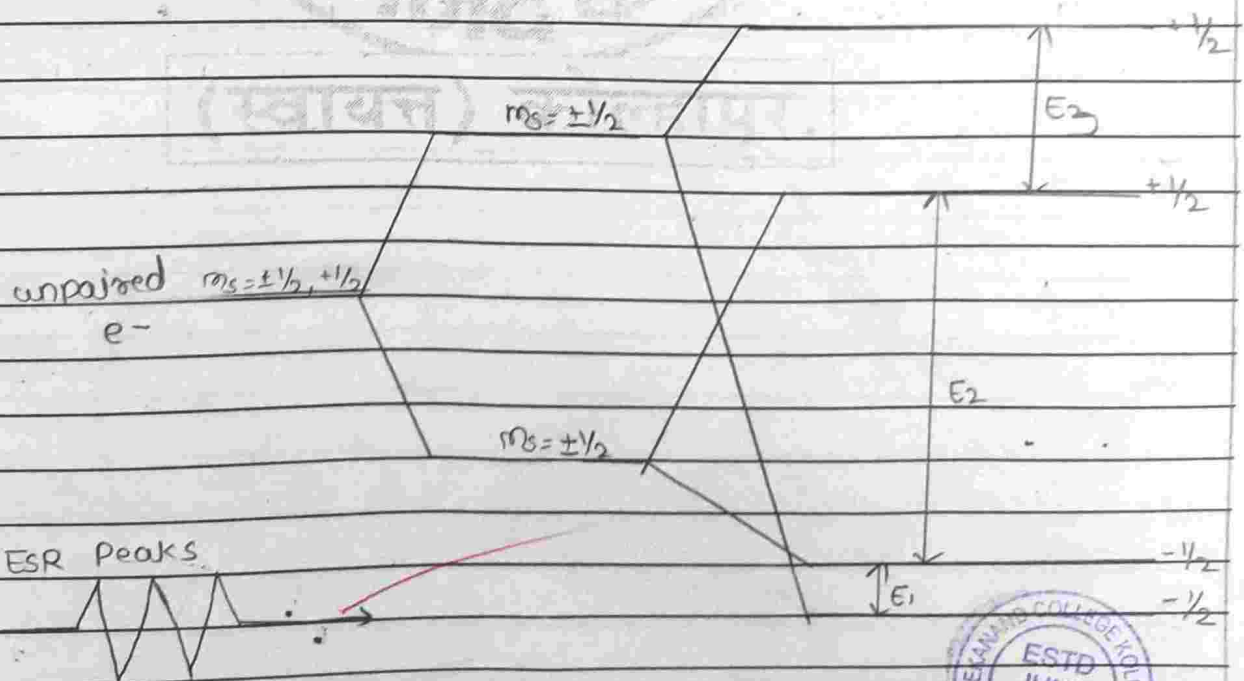
The all single is collect and they are singled by oscilloscope.



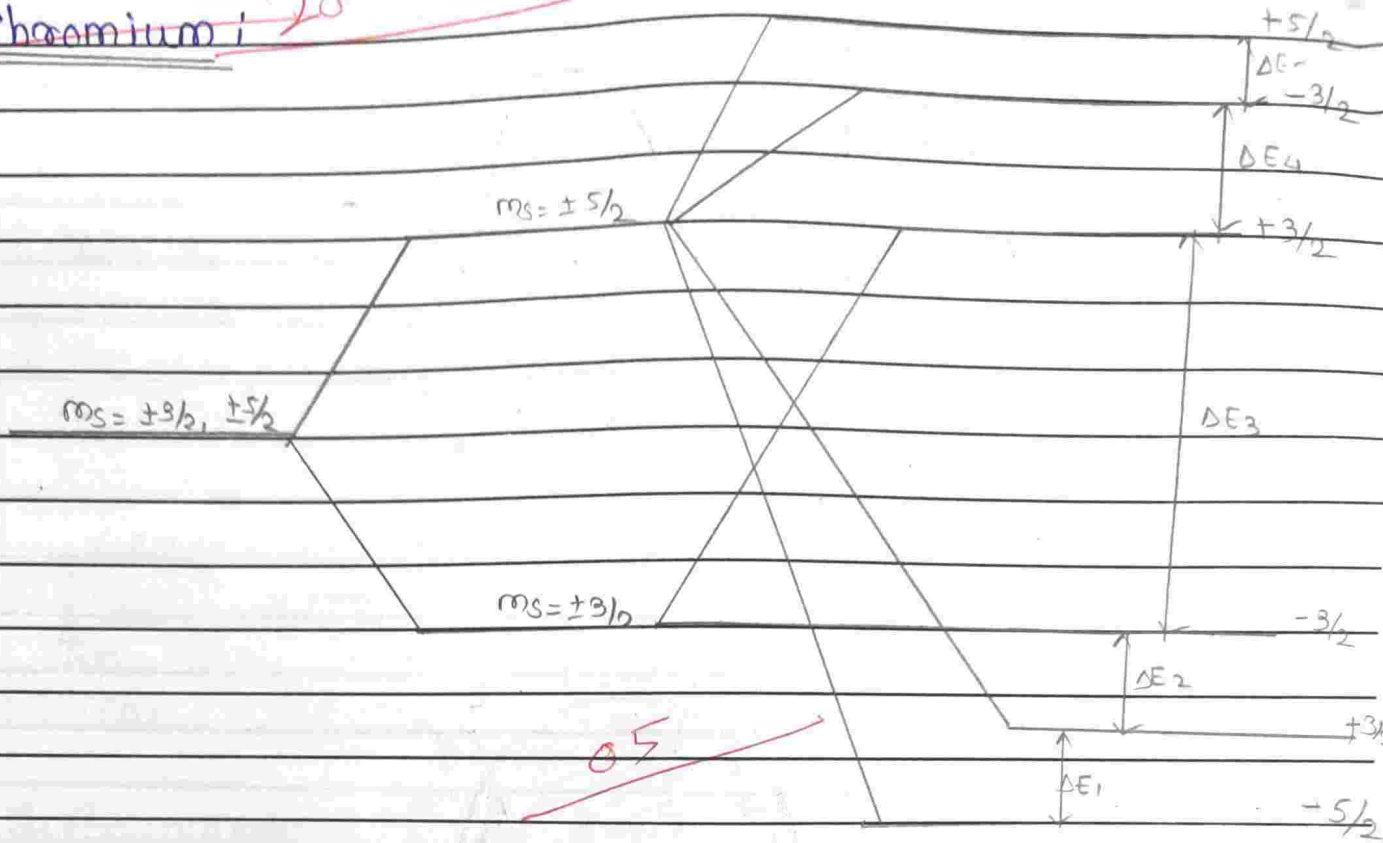


Q.3)

iron : $3d^5 4s^2$



2) Chromium $3d^5$



Seat No. _____

Vivekanand College, Kolhapur (Autonomous).

M. Sc. Part-II (Semester- III) Internal Examination Oct/Nov.2022

Subject: Physics

Title: Semiconductor Physics

Total Marks: 20

Time: 12.00 – 1.00 PM

- Instructions:** 1) All questions are compulsory.
2) Figures to the right indicate full marks.
3) Figures to the right indicate full marks.
4) Use of Scientific calculator or Log table is allowed.

(05)

Q. 1 Select most correct alternative

- The energy released per fission of uranium is about
a) 100 MeV b) 200 MeV
c) 400 MeV d) 150 MeV
- For flat spiral spring the angle between plane of spring and axis is
a) 60° b) 45° c) 90° d) 180°
- X-rays are the waves
a) electromagnetic b) longitudinal c) mechanical d) elastic
- According to Weins displacement law.....
a) $\lambda T_{\max} = \text{constant}$ b) $\lambda T = \text{constant}$
c) $\lambda_{\max} T = \text{constant}$ d) $\lambda_{\min} T = \text{constant}$
- A perfectly black body is.....concept.
a) an ideal b) a practical
c) an achievable d) none of these

(10)

Q2: Attempt any ONE.

- Derive the expression for Frenkel defect
- Derive an expression of intrinsic semiconductor for n-type material.

Q3: Attempt any ONE.

- Explain Bragg's law in reciprocal lattice
- Explain construction and working of UJT

(5)



"Dissemination of Education for Knowledge Science and Culture"
-Shikshanmaharshi Dr. Babuji Salunkhe

Shri Swami Vivekanand Shikshan Sanstha's
Vivekanand College (Autonomous) Kolhapur
Department of Physics M.Sc. II
2022-23

Attendance Sheet
Paper: Solid State Physics-II
Date: 29/11/2022

Roll. No.	Name Of Candidate	Sign
1	Kshirsagar Vijaya Suresh	<i>[Signature]</i>
2	Kumbhar Pooja Prakash	<i>[Signature]</i>
3	Kurade Shubhangi Shivaji	<i>[Signature]</i>
4	Latthe Sammed Rajendra	<i>[Signature]</i>
5	Nikam Mrunali Tanaji	<i>[Signature]</i>
6	Patil Aakansha Bhimarao	<i>[Signature]</i>
7	Patil Anuja Dattajirao	<i>[Signature]</i>
8	Patil Rajat Jaywant	<i>[Signature]</i>
9	Patil Sanyogita Sanjay	<i>[Signature]</i>
10	Patil Shrutika Jaysing	<i>[Signature]</i>
11	Pirale Siddhant Deepak	<i>[Signature]</i>
12	Rajguru Supriya Dhanaji	<i>[Signature]</i>
13	Rajput Prerana Pundlik	<i>[Signature]</i>
14	Sakate Santosh Shripati	<i>[Signature]</i>
15	Sayyad Alsaba Javed	<i>[Signature]</i>
16	Shelar Avinash Sanjay	<i>[Signature]</i>
17	Sonkamble Rohan Raju	<i>[Signature]</i>
21	Sutar Pooja Vishwanath	<i>[Signature]</i>
22	Gaikwad Aishwarya Suryakant	<i>[Signature]</i>
23	Chougule Shraddha S.	<i>[Signature]</i>
24	Gaikwad Divya Ramesh	<i>[Signature]</i>
26	Gavade Sayali Shantaram	<i>[Signature]</i>
27	Gurav Rutuja Ravindra	<i>[Signature]</i>
28	Hirave Pravin Prakash	<i>[Signature]</i>
29	Jadhav Nikhil Sandeep	<i>[Signature]</i>
30	Jamadar Wahida Sardar	<i>[Signature]</i>
31	Kukade Seema Vishnu	<i>[Signature]</i>
32	Khandekar Pooja Sanjay	<i>[Signature]</i>
33	Khokar Raez Rafiq	<i>[Signature]</i>
34	Khot Priyanka Balaso	<i>[Signature]</i>
35	Kondare Adinath Bhaskar	<i>[Signature]</i>
36	Kore Jyoti Vinayak	<i>[Signature]</i>



Shubhangi Shivaji Kurade

D-16-11-22

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VIVEKANAND COLLEGE, KOLHAPUR (AUTONOMOUS)

SUPPLIMENT

Signature
of
Supervisor

Suppliment No. : 1

Roll No. : 1350

Class : M.Sc II

Subject : Solid state physics II

Test / Tutorial No. : Internal exam.

Div. :

19
20

Q.1

1) In a 1 cm^3 piece of metal, we have nearly 10^{22} electrons per cm^3 .

2) NaCl is an Insulator.

3) As the interatomic spacing ~~increases~~ ^{decreases}, energy level turns into continuous bands.

4) AlAs is an indirect SC with Band gap 2.16 eV.

5) The fermi dirac distribution law for probability of finding e^- in energy level E is given by

$$\frac{1}{1 + e^{(E-E_F)/kT}}$$



e) Electrons and holes in quantum well.

1) Direct and Indirect semiconductor:

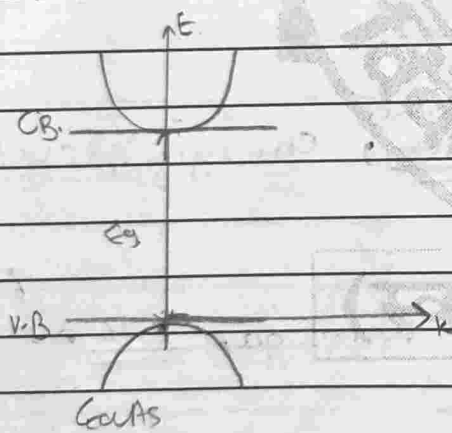
According to the Bloch theorem:

$$\frac{\hbar^2 k^2}{2m} + U(r) + \psi(r) = E \psi(r)$$

The Energy of (E) and potential energy diagram it states that the

There are two types of semiconductors: Direct and indirect semiconductors.

1) Direct semiconductor:



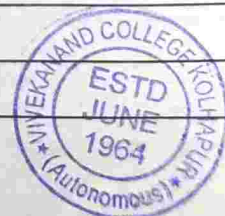
1) In direct semiconductor transition between the minima of the conduction band to the maxima of a valence band with same k values.

2) k values of the direct semiconductors are same.

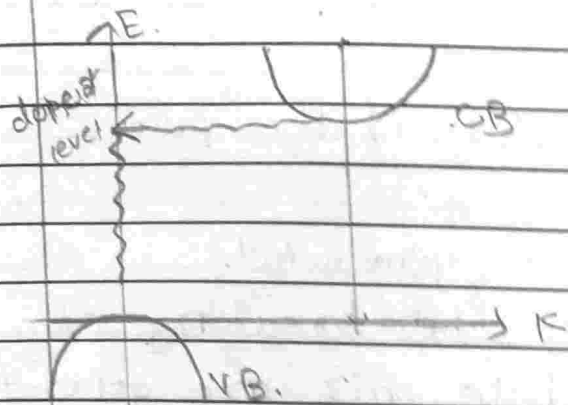
3) In direct semiconductor energy and momentum of electron are conserved.

4) In direct semiconductor Radiative recombination are observed.

5) e.g. GaAs.



2) Indirect Semiconductors :



1) In indirect semiconductors transition between minima of the Conduction Band to maxima of valence band with different k values.

2) In indirect semiconductor k values are different.

3) In indirect Semiconductors neither energy nor momentum ~~are~~ of e^- are non-conserved.

4) In indirect semiconductor non-radiative recombination observed.

5) e.g. AIAs.

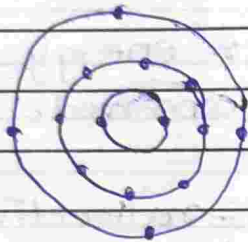
Q. 9



Q. 3

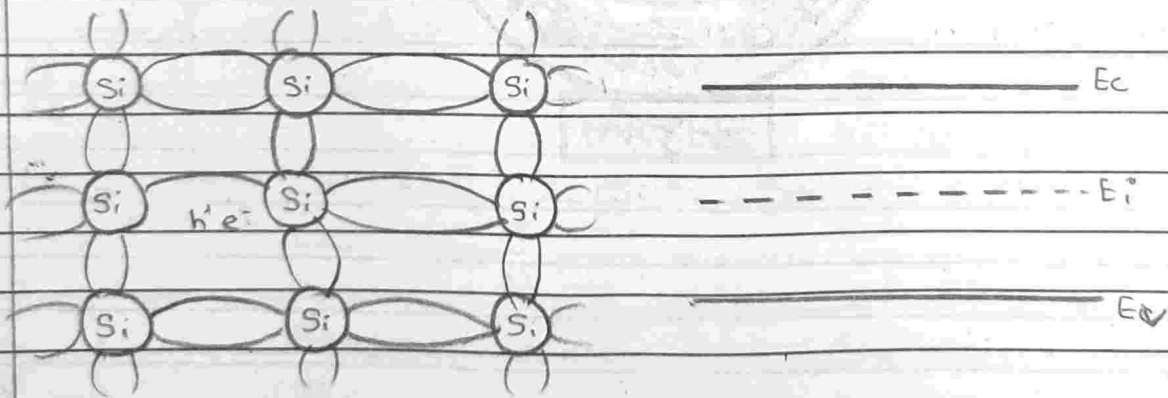
1) Intrinsic Semiconductor :-

- Intrinsic semiconductor is the pure form of semiconductor.
- Electron and hole pairs are generated.
- Intrinsic semiconductor due to the breaking of bonding their are electron hole pair are generated
- e.g. of Silicon.
- Atomic no. of Silicon is 14



Silicon is tetravalent atom.

- In intrinsic semiconductor Silicon atom are covalent pair to neighbouring 4 atoms.



at 0K.

Band Structure

concentration of e^- in conduction band is equal to the concentration of holes in valence band.

$$\text{Conc. of } e^- (n) = \text{conc. of hole}$$
$$n_i = p_i$$



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SUPPLIMENT

Suppliment No. : 2

Roll No. : 1350

Class : M.Sc II

Signature
of
Supervisor

Subject :

Test / Tutorial No. :

Div. :

rate of recombination (r_i) = rate of generation (g_i)

- In Intrinsic Semiconductor materials ~~are~~ rate of g_i & r_i are time dependent.
- The rate of g_i increase then with time.

Extrinsic Semiconductor :

Adding impurities in pure semiconductor to their conductivity they called doping.

In extrinsic semiconductor adding impurities with doping there are 2 types of extrinsic SC.

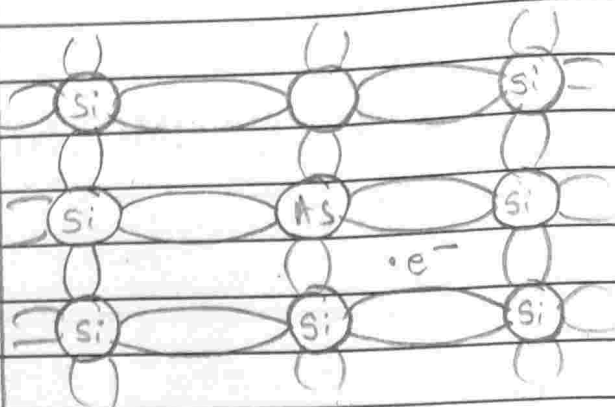
1) n-type Semiconductor :

In n-type semiconductor pentavalent impurity added to the pure semiconductor.

e.g. Arsenic, II

Silicon atom is doped with pentavalent valent impurity like Arsenic.

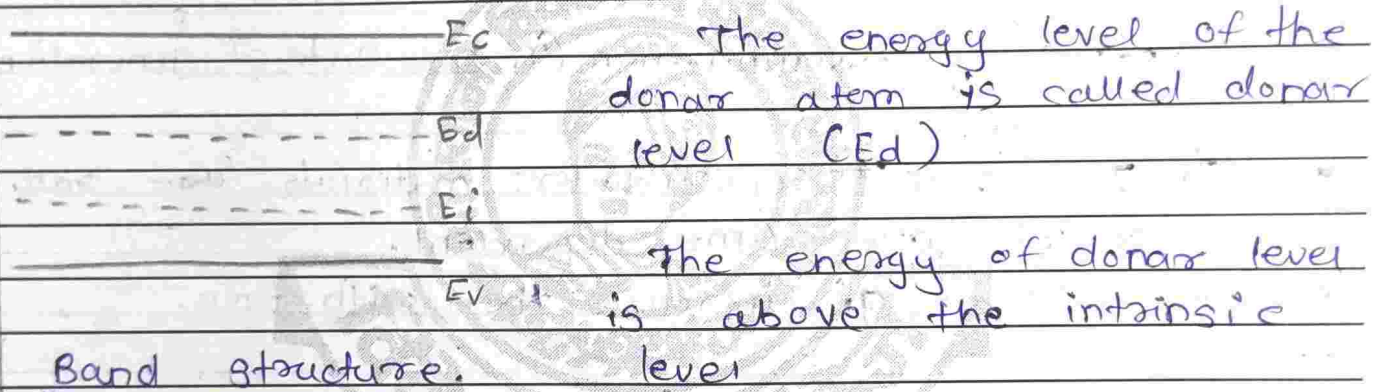




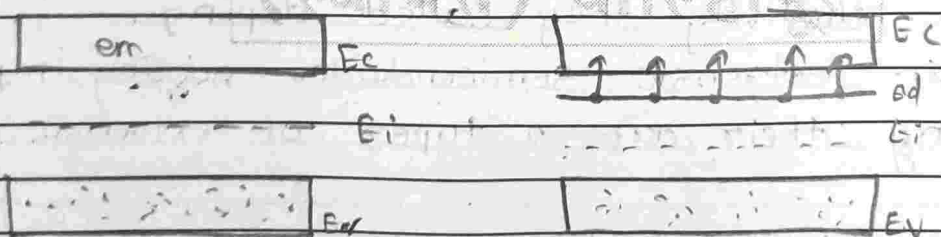
• n-type sc. Si atom are pairing of e^- with neighbouring 4 atoms.

• n-type Semiconductor are $-ve$ charged.

- In n type semiconductor electrons are donate to the other atoms.
- Then the n-type Semiconductor is donor atoms.



- The n-type Semiconductor are near to the CB of intrinsic semiconductor.



at 0K

at 50K

- n type Semiconductor having filled with e^- at 0K.
- at low temp (50 - 100 K) e^- are bounded to conduction band.

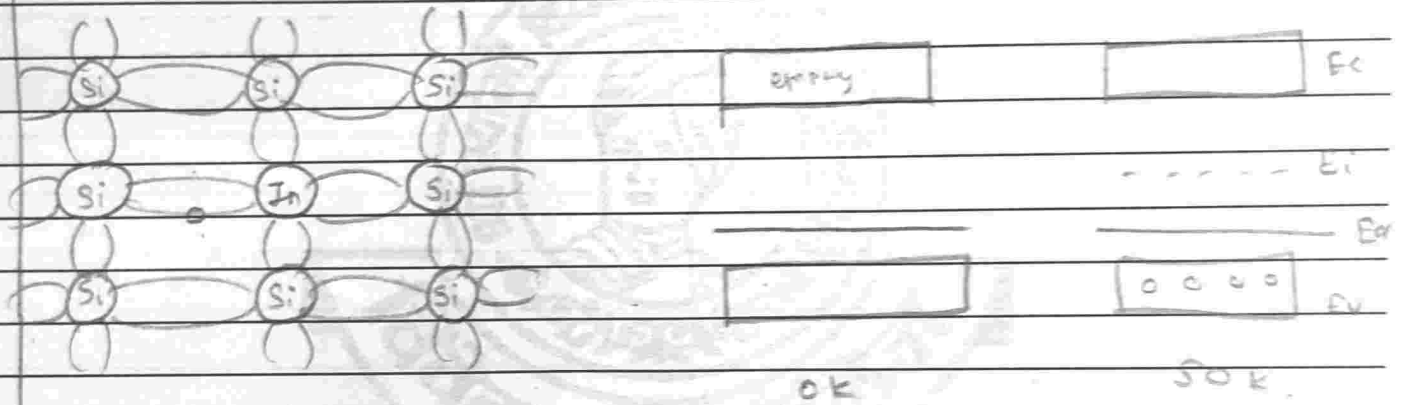


- It is the e^- are majority charge carriers.

2) p-type Semiconductor.

In p-type trivalent impurity added to the pure semiconductor.

e.g. Al, Indium, Gallium, Bismuth



p-type Semiconductor are holes majority.

- In p-type Semiconductor holes are majority charge carriers and e^- are minority charge carriers.
- In p-type Semiconductor the atoms are accept the electron then it is called acceptor atom.
- Energy of the p-type SC are near to the valence band.
- Energy of the acceptor atom are known as acceptor level (E_A).
- In p-type semiconductor majority are holes.
- e^- are ~~in~~ jump to CB from valence holes are created.



iv) ~~is~~ Amphoteric Materials :-

$$p_o \gg n_o$$

$$n_o \gg h_i$$

$$n_o p_o = n_i^2$$

mass action law

This obeys both intrinsic & extrinsic S.C.



Miss. Bijanka Balaso Khot

Date: 16/11/2022

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VIVEKANAND COLLEGE, KOLHAPUR (AUTONOMOUS)

SUPPLIMENT

Signature
of
Supervisor

Suppliment No. :

Roll No. : 1344

Class : M.Sc-II

Subject :

Test / Tutorial No. :

Div. :

19
20

Q.1

1) c) 10^{23}

2) b) Insulator

A

3) b) Increases

4) d) 2.16

5) a) 1

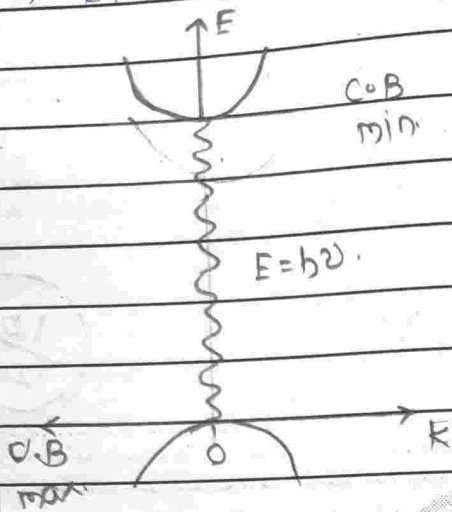
$$1 + e^{(E-E_F)/kT}$$



Q.2

1) Direct and Indirect Semiconductors:

a) Direct Semiconductors:



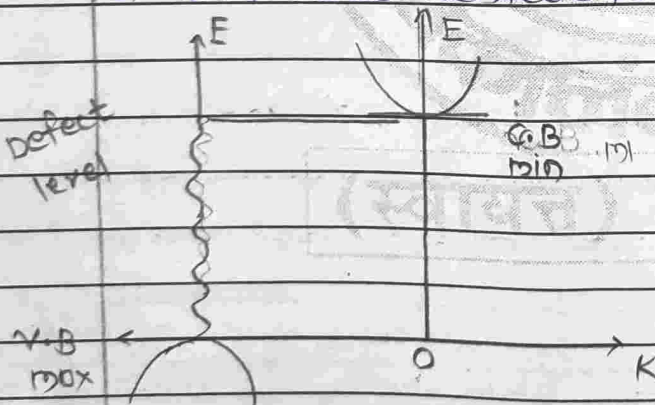
① The transition of semiconductor from the maximum of conduction band value to the maximum of conduction band value occurs at same k value ($k=0$). This is called as direct semiconductor.

② The transitions usually as a radiative recombination. It is used in LED's Laser, etc.

③ The energy and angular momentum of an electrons is conserved.

④ eg. GaAs, AlAs, etc.

b) Indirect Semiconductors:



① The transition of semiconductor from the maximum of valence band to the minimum of conduction band occurs at different k value. It is called as indirect semiconductor.

② The transitions usually as non-radiative recombination.

③ In this transitions, neither energy nor angular momentum conserved.

④ ex. GaP, AlAs, B etc.



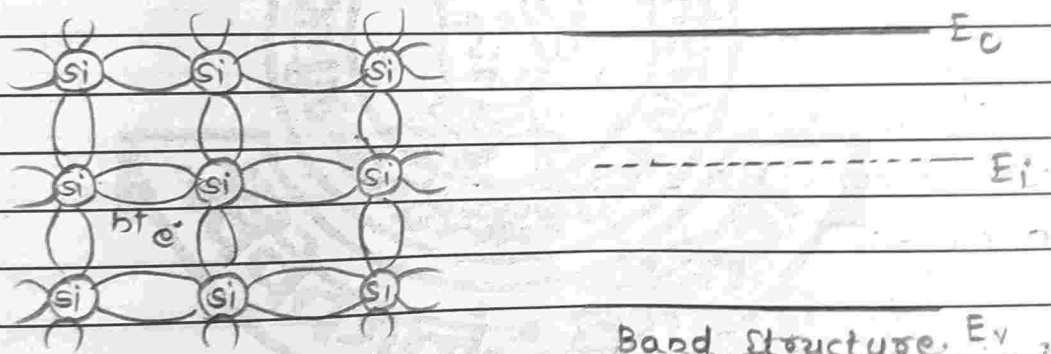
① Extrinsic and Intrinsic Semiconductors :

① The Intrinsic Semiconductors :

A perfect semiconductor with no impurities or lattice defects is called as intrinsic semiconductor.

- At 0K, valence band completely filled and conduction band is completely empty. Therefore, there is no charge carriers at 0K.

- But Higher temperature, electron-hole pairs are created. Therefore, the electrons are excited to the conduction band the ~~be~~ across to the band gap to the conduction band. Therefore, electron-hole pair is a charge carrier in intrinsic semiconductor.



Intrinsic semiconductor

The electron-hole pairs are generated due to the breaking of co-valent bond in crystal lattice of pure semi-conductor.

- The energy required to break the bond is band gap energy.

- Since, the electron-hole pair is created as the concentration of e^- s in conduction band is equal to the concentration of holes in valence band.

$$\therefore n = p = n_i$$

where,

n_i = Intrinsic carrier concentration.



In steady state, we must have rate of generation,
 $g_i = \text{rate of recombination } (\tau_i)$

where,

τ_i, g_i are temperature ~~temp~~-dependent

At any temperature, the rate of recombination (τ_i) is directly proportional to the equilibrium concentration of electrons and holes.

$$\therefore \tau_i \propto n_0 p_0$$

where,

$n_0 p_0$ is ~~eq~~ equilibrium concentrations of e's and holes

$$\therefore \tau_i = \alpha \tau \cdot n_0 p_0$$

$$= \alpha \tau \cdot D_i^2$$

$$\therefore \tau_i = \alpha \tau \cdot D_i^2$$

where,

$\alpha \tau$ is constant of

which depends on the mechanism of recombination occurs.

Extrinsic Semiconductor:

The process of adding an impurity to pure semiconductor to improve its conductivity is called as doping.

n-type sc:

When a pure semiconductor is doped with pentavalent impurity atoms like As, Sb, etc. They have an extra energy level nearer to the conduction band of pure semiconductor.

- At 0K, this impurity levels are filled with electrons. But at low temperature (50K-100)K, the electrons are excited to the conduction band. This level is called

